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PATENT APPLICATION



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Satoshi TATSUURA et al.

Group Art Unit: 1753

Application No.: 10/082,228

Examiner: E. Wong

Filed: February 26, 2002

Docket No.: 106200.01

For: METHOD FOR ELECTRODEPOSITED FILM FORMATION, METHOD FOR ELECTRODE FORMATION, AND APPARATUS FOR ELECTRODEPOSITED FILM FORMATION

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

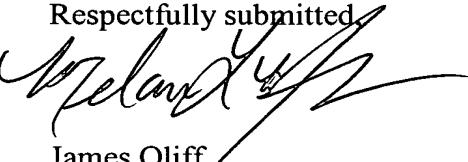
In reply to the December 9, 2003 Restriction Requirement, Applicants provisionally elect Group III, claims 30 and 31, with traverse.

Elected claims 30 and 31 are directed to an apparatus for electrodeposited film formation comprising a laser device for irradiating the object to be treated with a pulse laser whose pulse width is less than a picosecond to thereby excite electrons in the laser-irradiated part to cause the electrodeposited film to be formed in the laser-irradiated part. The independent claims of non-elected Groups I and II are both directed to a method for electroformation comprising irradiation with a pulse layer whose pulse width is less than a picosecond. Based on the similarities between the elected and non-elected claims, it is respectfully submitted that the subject matter of all claims 5-9, 11, 12, 14, 16, 18, 20, 21, 23, 24, 26 and 28-31 is sufficiently related that a thorough search for the subject matter of any one Group of claims would encompass a search for the subject matter of the remaining

claims. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it is stated that "if the search and examination of an entire application can be made without serious burden, the examiner must examine it on the merits, even though it includes claims to independent or distinct inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicants and duplicative examination by the Patent Office.

Thus, withdrawal of the Restriction Requirement is respectfully requested.

Respectfully submitted,



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Date: January 8, 2004

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